

The background of the slide is a complex, light gray particle detector simulation. It features a central point from which numerous tracks radiate outwards. These tracks are composed of small, rectangular blocks, likely representing detector elements or pixels. The tracks are dense and intricate, with many overlapping paths, creating a sense of depth and complexity. The overall appearance is that of a high-energy physics experiment's data visualization.

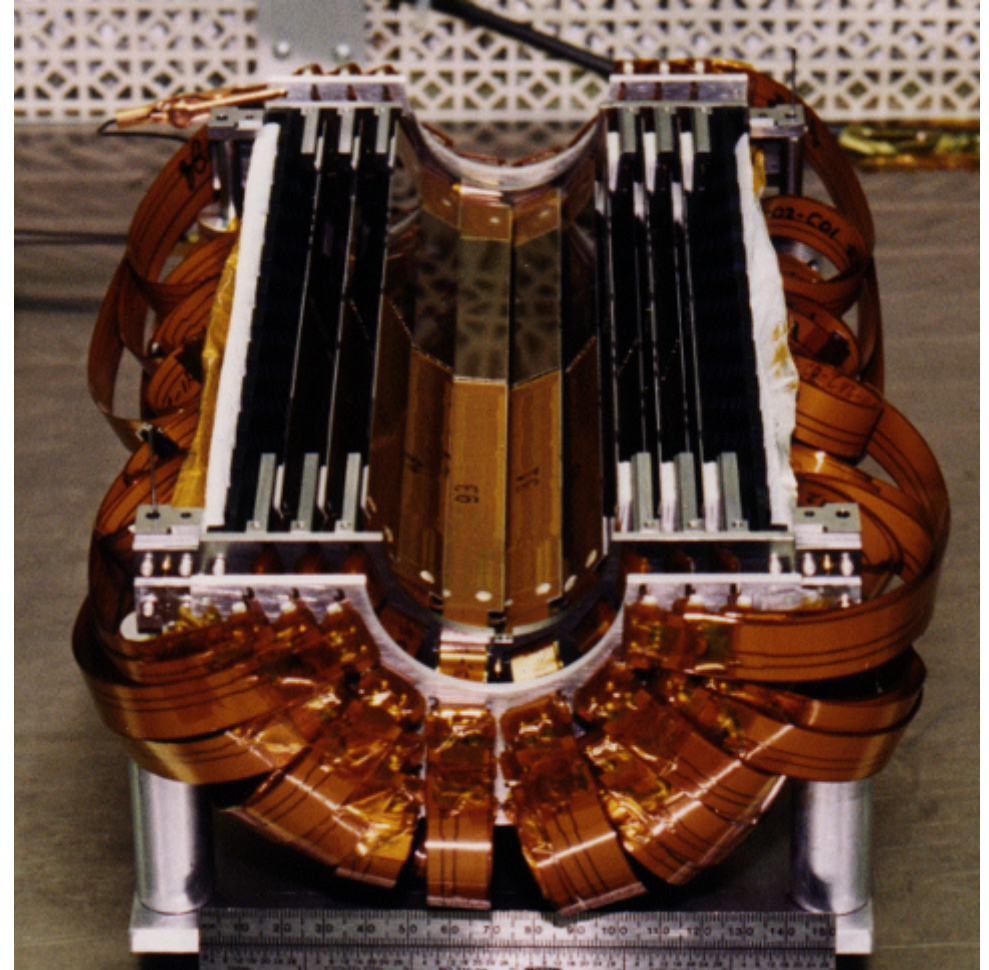
Pixel Technologies for the ILC

Marcel Stanitzki

STFC-Rutherford Appleton Laboratory

In the beginning ...

- SLD's VXD3
 - 307 Million channels
 - 20 μm pixels
- The Grandfather of all LC pixel detectors
- Still provides valuable "lessons learned" from SLC
- Starting point for ILC pixel R&D



Pixel RD for the ILC

- Very active field for the last ten years
- Plenty of groups involved in all the regions
- A lot of progress has been made
 - Enough material for several long talks
 - Need to down-select ...
- In this talk, I'll focus on
 - Pixel technologies
 - Silicon-only pixels
- Apologies in advance for omissions ...



ILC Detector Requirements

- Impact parameter resolution • Need factor 3 better than SLD

$$\sigma_{r\phi} \approx \sigma_{rz} \approx 5 \oplus 10 / (p \sin^{3/2} \theta)$$

$$\sigma_{r\phi} = 7.7 \oplus 33 / (p \sin^{3/2} \theta)$$

- Momentum resolution • Need factor 10 (3) better than LEP (CMS)

$$\sigma \left(\frac{1}{p_T} \right) = 5 \times 10^{-5} \text{ (GeV}^{-1}\text{)}$$

- Jet energy resolution goal • Need factor 2 better than ZEUS

$$\frac{\sigma_E}{E} = \frac{30\%}{\sqrt{E}}$$

$$\frac{\sigma_E}{E} = \frac{60\%}{\sqrt{E}}$$

- Detector implications
 - Calorimeter granularity
 - Pixel size
 - Material budget, central
 - Material budget, forward
- Detector implications
 - Need factor ~ 200 better than LHC
 - Need factor ~ 20 smaller than LHC
 - Need factor ~ 10 less than LHC
 - Need factor $\sim >100$ less than LHC

Highly segmented, low mass detectors required -> pixels !

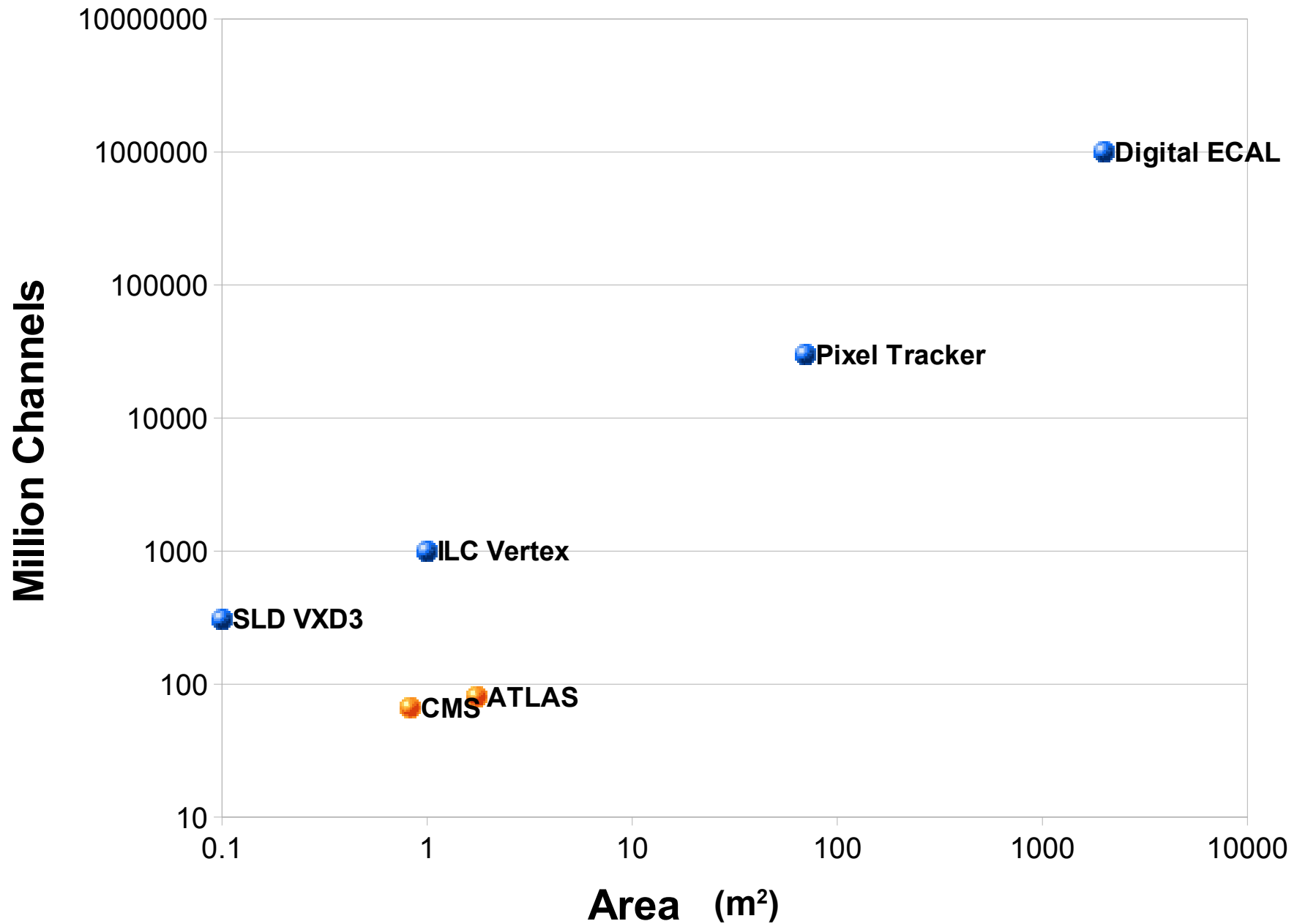


And the pixels spread ...

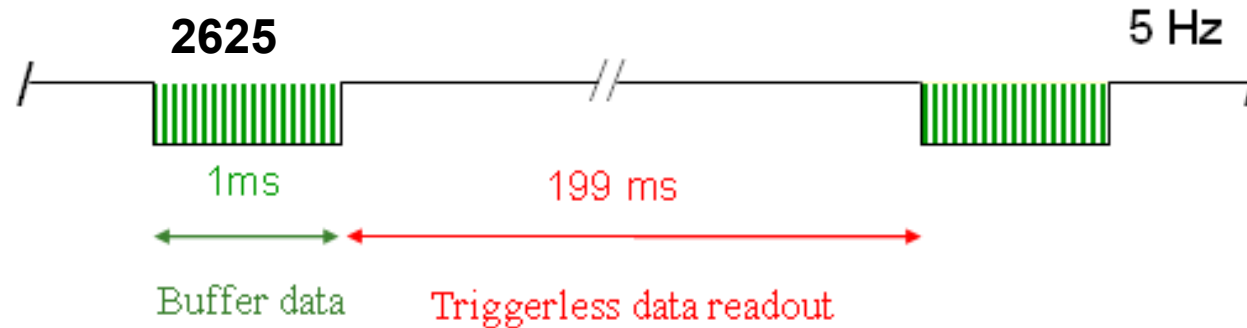
- Pixels originally only intended for vertex detectors
 - like SLD ...
- But pixels are becoming affordable
 - Pixel detectors spread outwards
- Silicon pixel trackers are now feasible
 - $\sim 70 \text{ m}^2$ silicon , 30 Gigapixel
- Digital EM calorimetry using pixels as particle counters
 - See talk by Nigel Watson
 - 2000 m^2 area, 1 Terapixel



Pixels everywhere ...



ILC timing



- ILC environment is very different compared to LHC
 - Bunch spacing of ~ 300 ns (baseline)
 - 2625 bunches in 1ms
 - 199 ms quiet time
- Occupancy dominated by beam background & noise
- Readout during quiet time possible

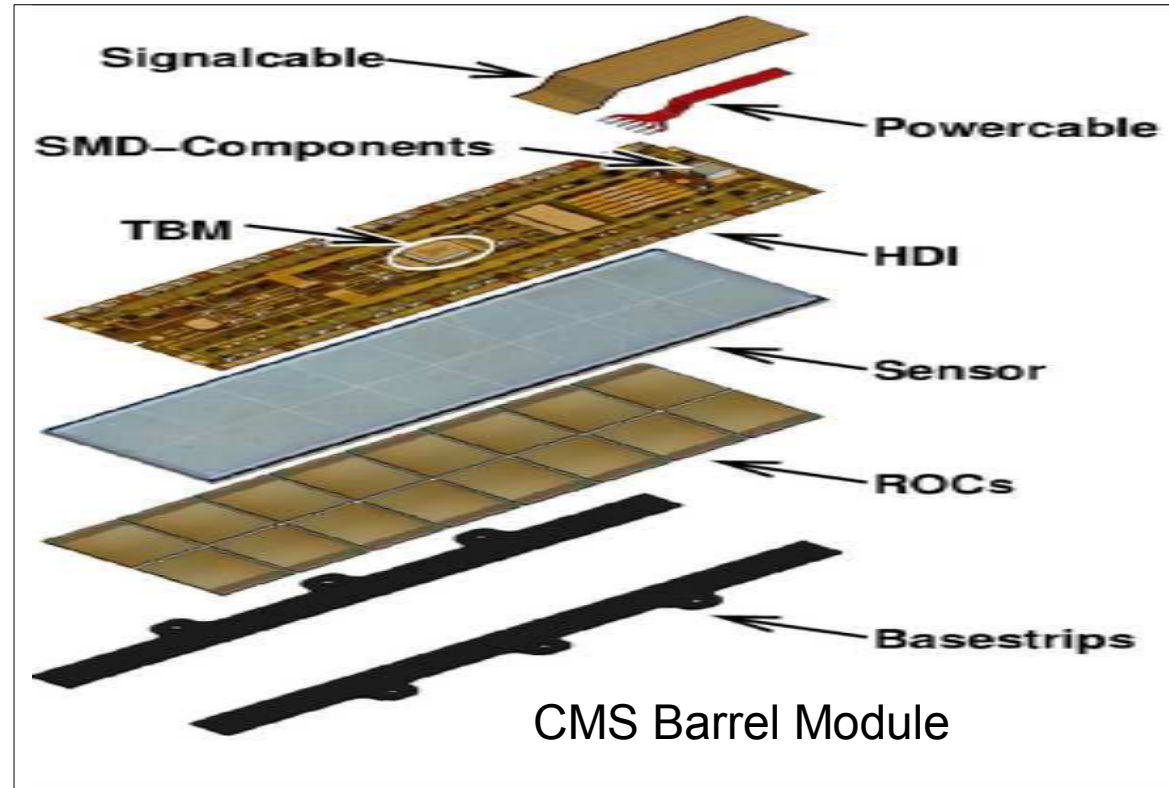
Pixel Timing & Readout

- Time sampling
 - single bunch resolution
 - buffer hits
 - readout during quiet time
- Time slicing
 - divide train in n slices
 - readout during train/quiet time
- Time-integrating
 - no bunch information
 - readout during quiet time
- On-Pixel processing
 - each pixel self-sufficient
 - digital data stream off pixel
 - minimal amount of interconnects
- Off-Pixel processing
 - data is moved to a readout chip
 - requires additional circuitry and interconnects

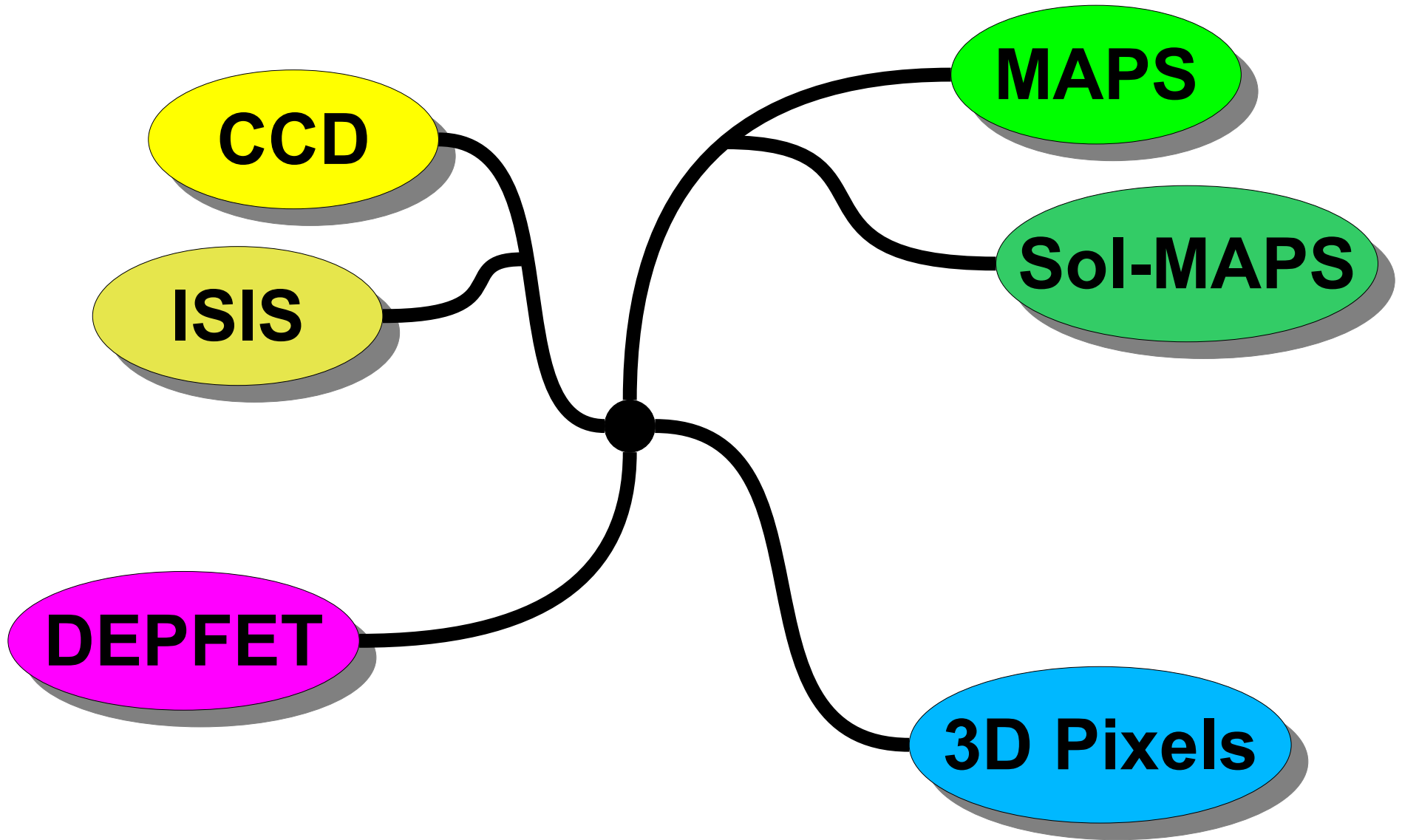


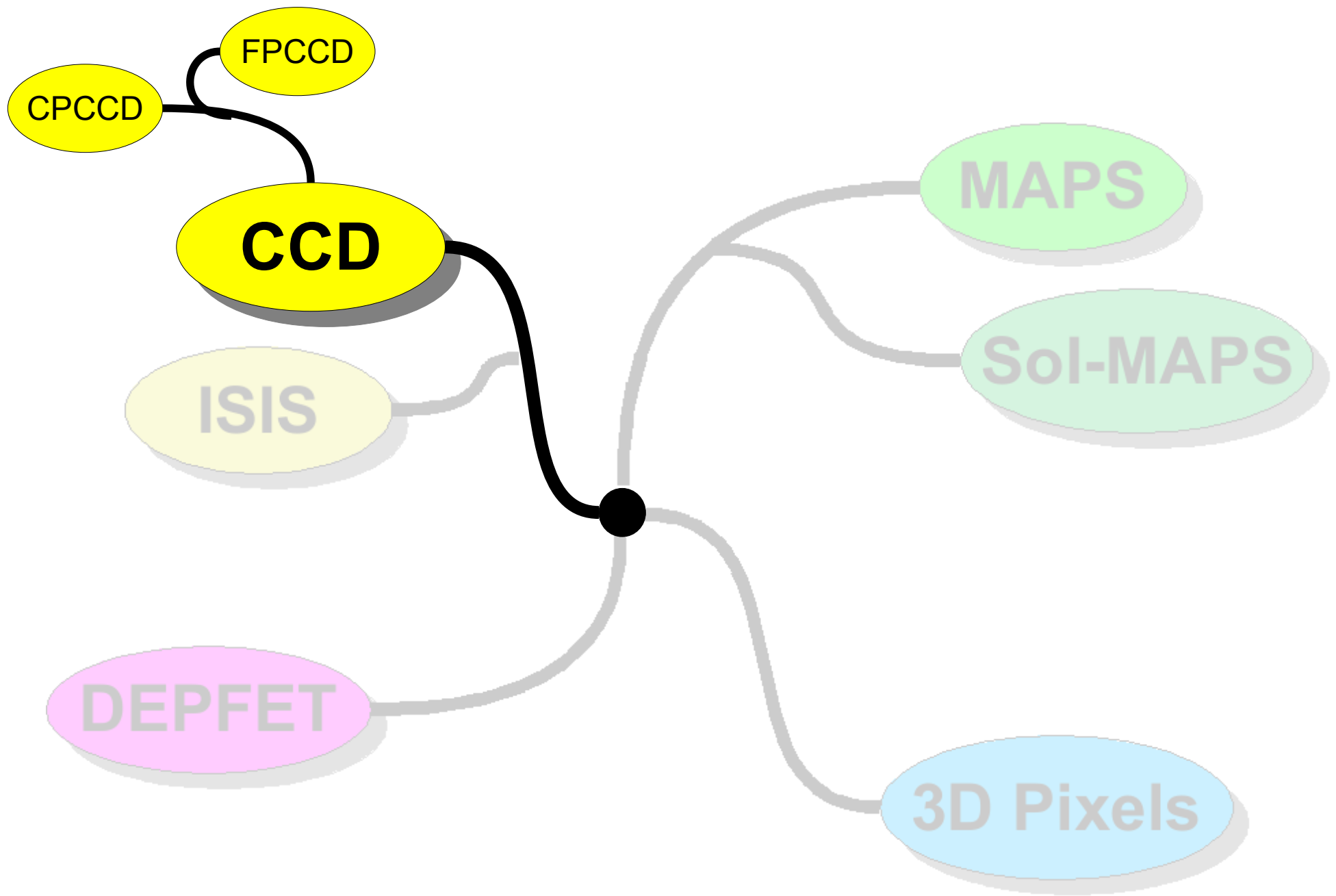
What about LHC pixels ?

- LHC requirements
 - extremely rad hard
 - very fast (25 ns)
- LHC pixels ..
 - "large"
 - cooling required
- ILC requirements
 - slow and not rad-hard
- ILC pixels
 - very low material budget
 - high granularity



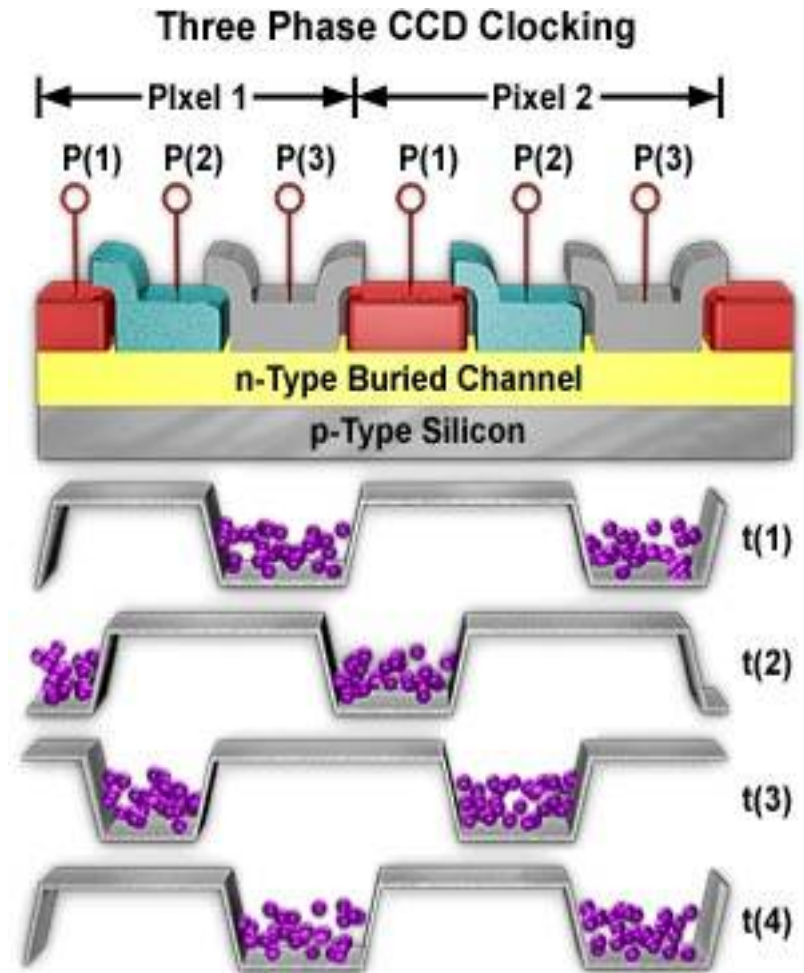
Pixel Technology Tree





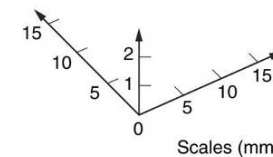
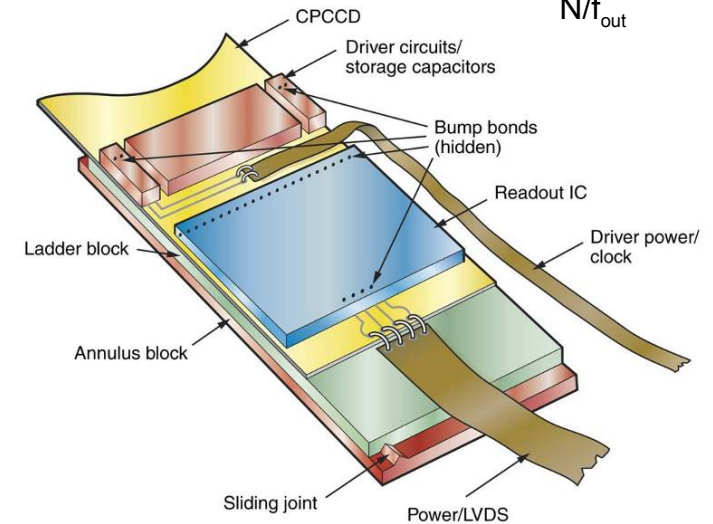
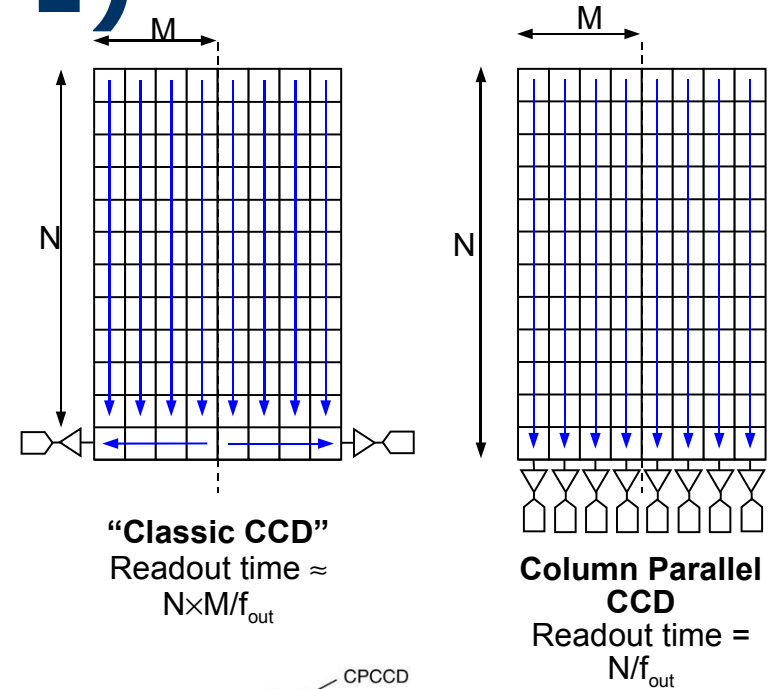
CCD's

- **C**harge-**C**oupled **D**evice
- Extensively used in imaging
- Established technology
- VXD3 used CCD's
- Basic working principle
 - charge storage
 - readout as bucket-chain
 - robust against pick-up
- Require
 - high charge transfer efficiency
 - cooling to -20 C
 - high drive currents

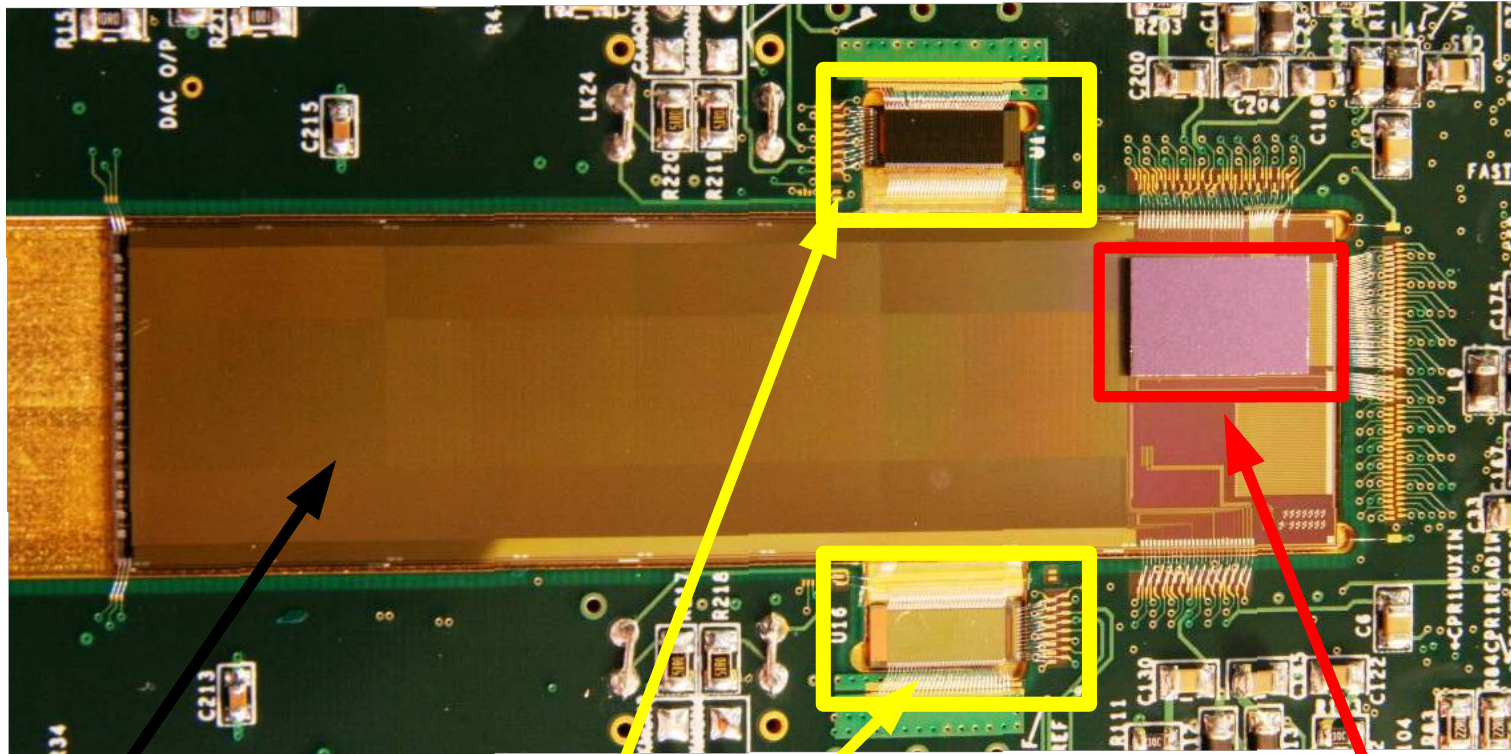


CPCCD (LCFI)

- “Classic ” CCD readout is slow
- **Column Paralled CCD**
- Idea: divide readout chain into columns
 - Higher speeds possible (50 MHz)
 - Time slicing approach (20 frames)
 - 20 μm pixels
- CPCCD requires a dedicated readout chip
- High currents driving the readout
- already second generation design



A CPCCD Module



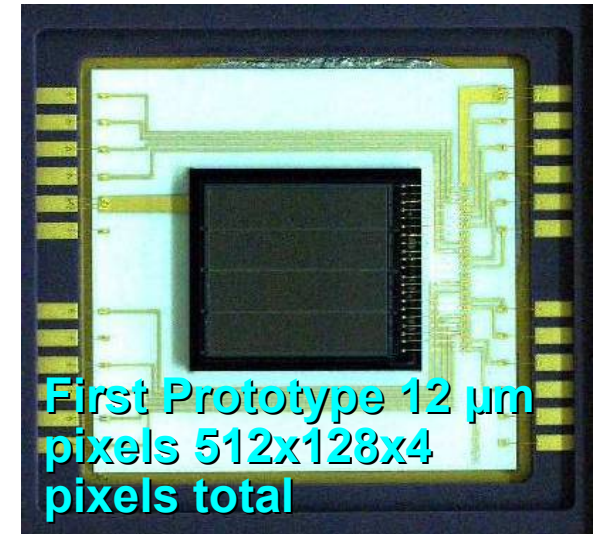
CCD

Driver Chips

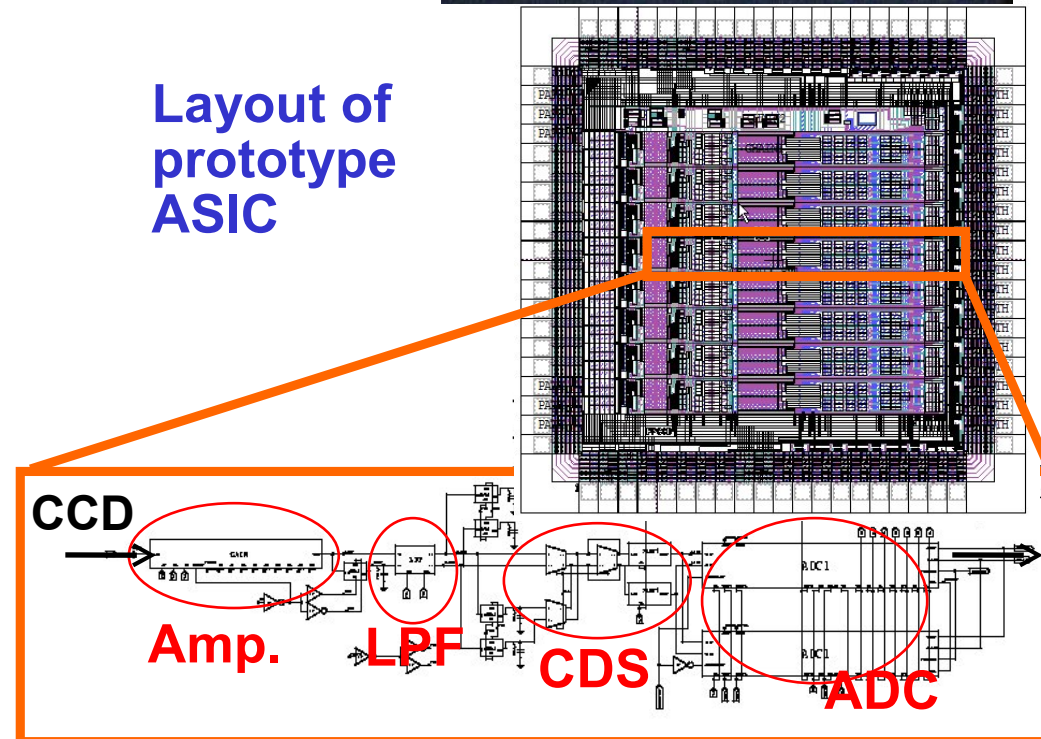
Readout
ASIC

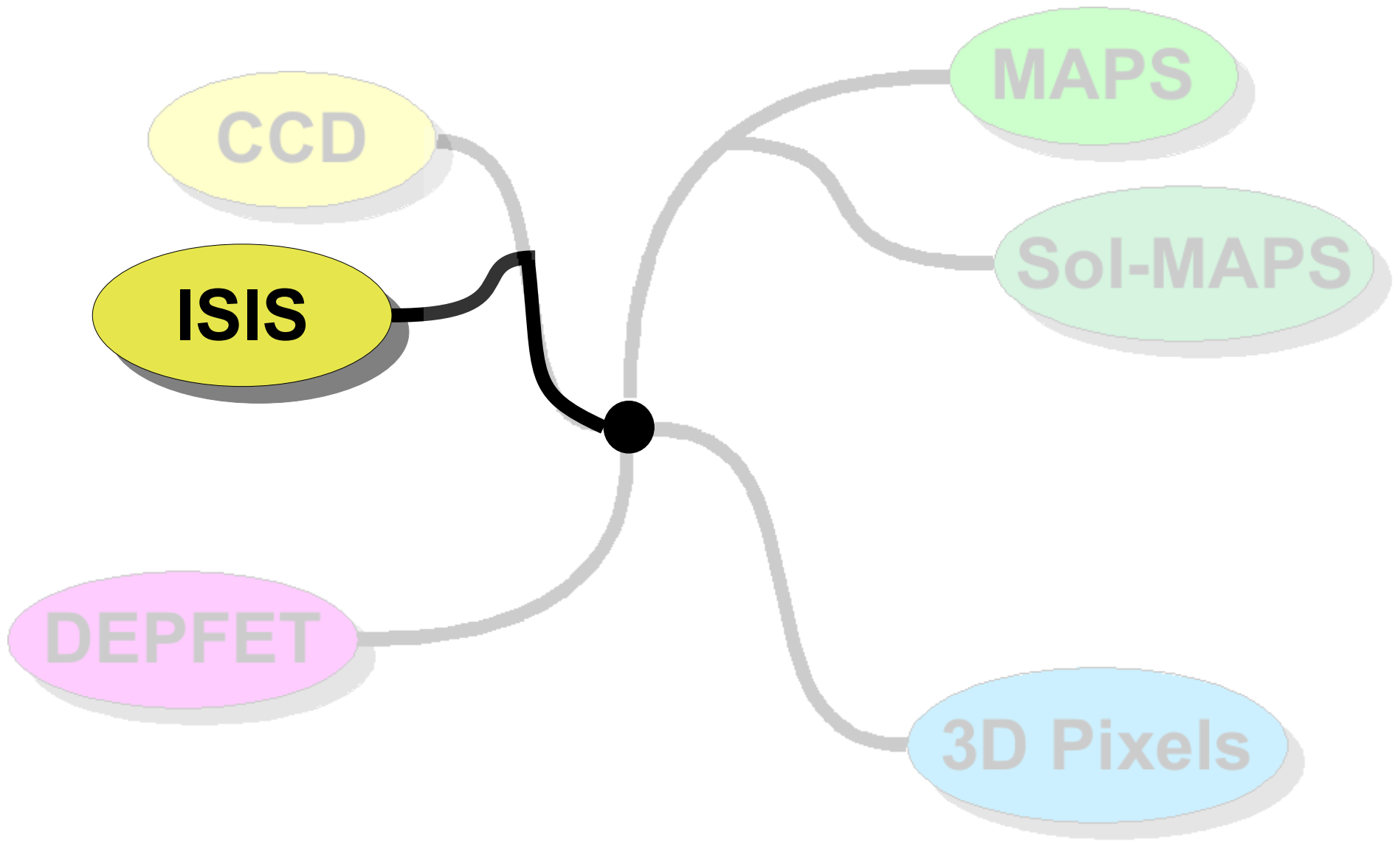
FPCCD (KEK et. al.)

- **Fine Pixel CCD**
- Time-integrating
 - Instead of time slicing ...
 - requires 5 μm pixels
- Fully depleted epitaxial layer
 - minimize the number of hits due to charge spread
- Requires cooling
- Readout similar to CPCCD
- currently 12 μm pixel size
 - Expect 5 μm pixels in 2011



Layout of prototype ASIC





ISIS (LCFI)

- **In Situ Image Storage**

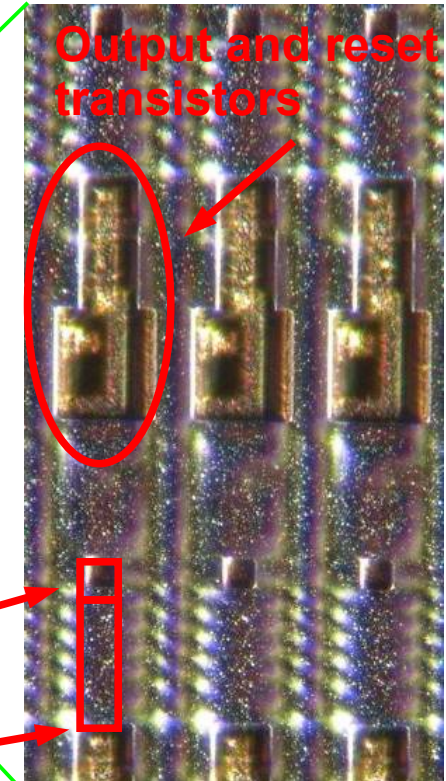
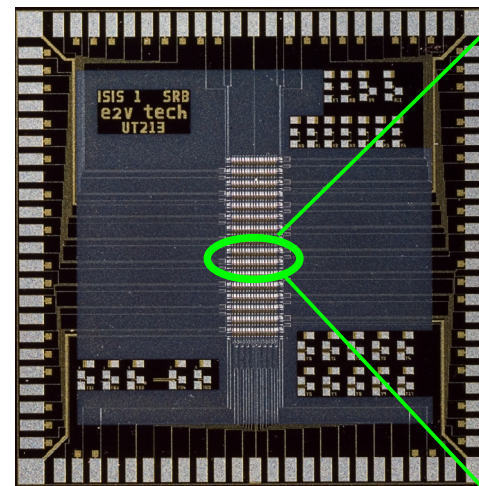
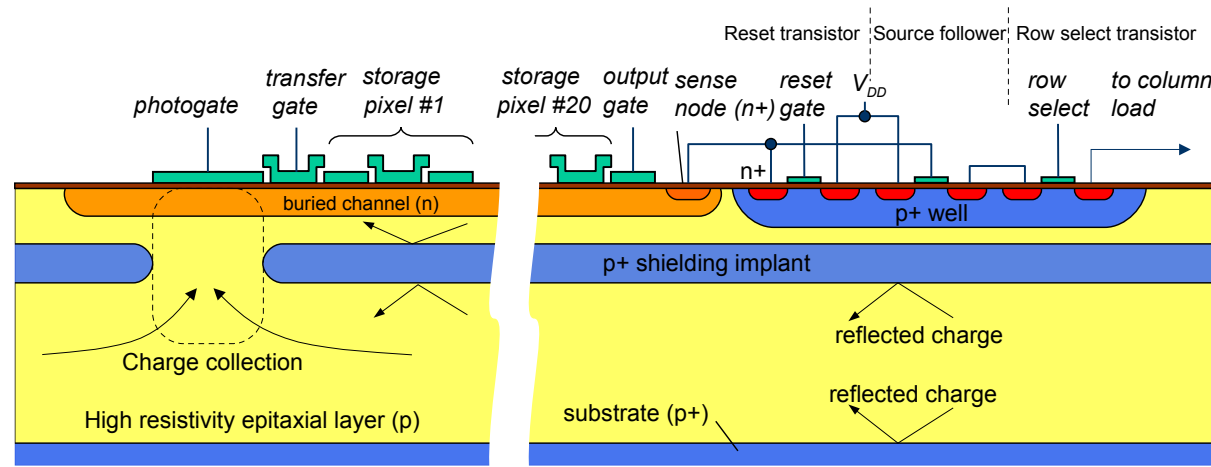
- charge collection with photo diode
- Transfer to CCD-like structure
- Time-slicing (20x)

- Readout chips separate

- semi-integrated pixels
- plans for full integration

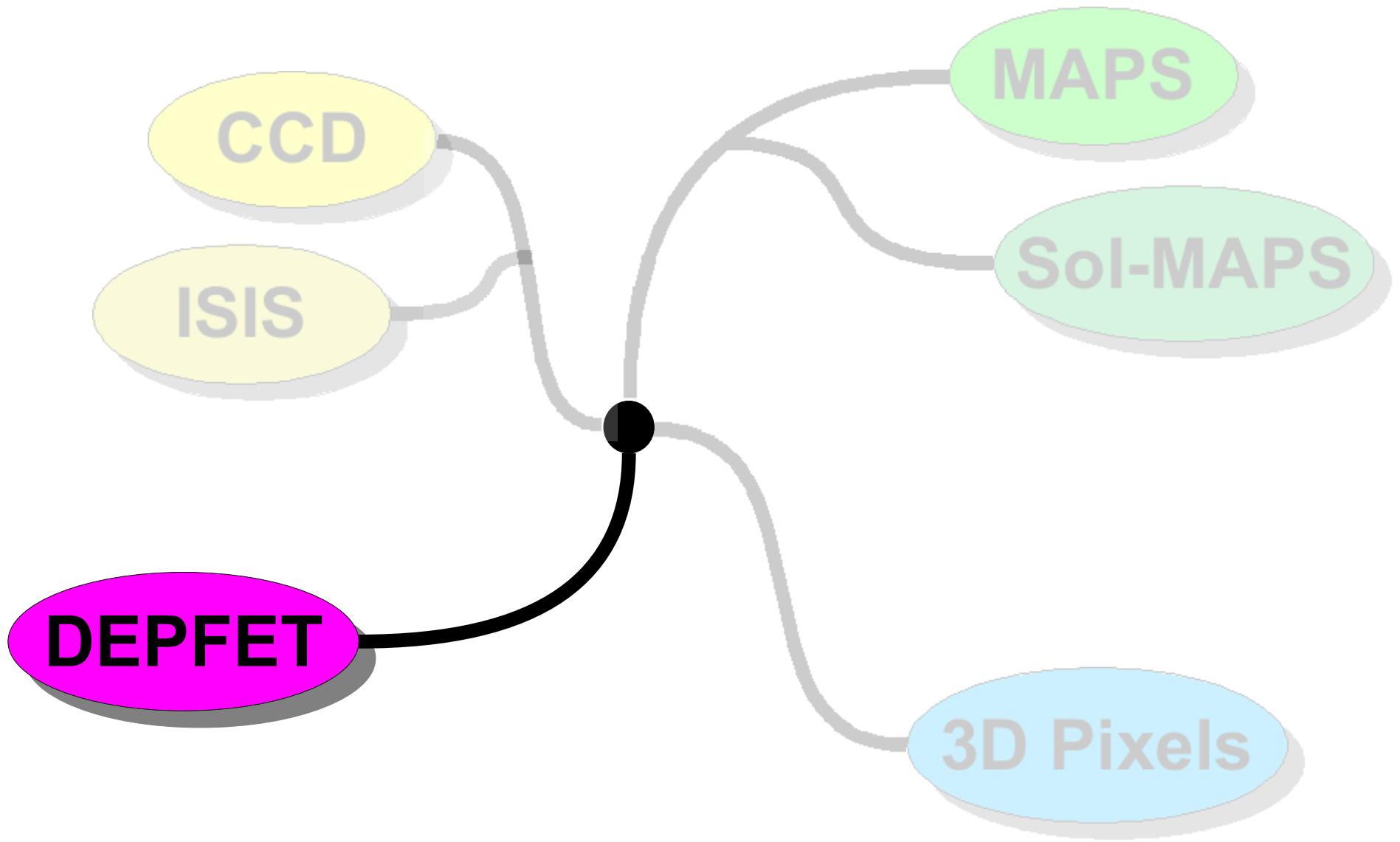
- First proof of principle devices

- ISIS1
- Successor ISIS2 has been shipped



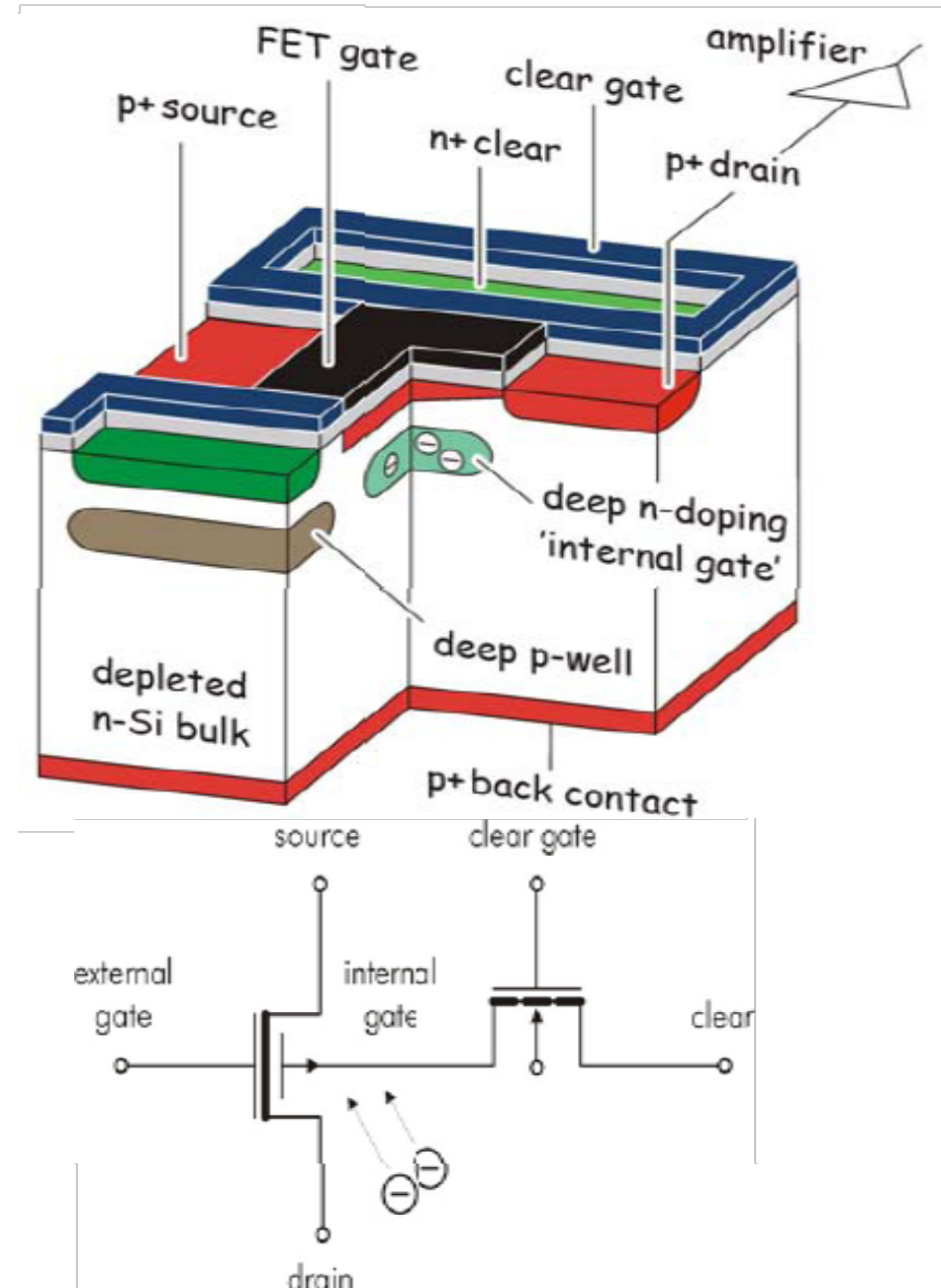
Photogate aperture (8 μm square)

CCD (5x6.75 μm pixels)



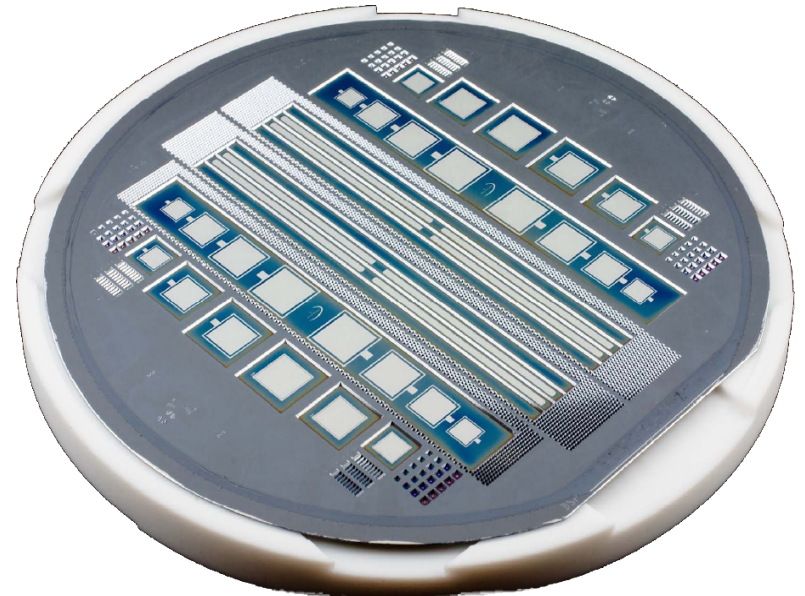
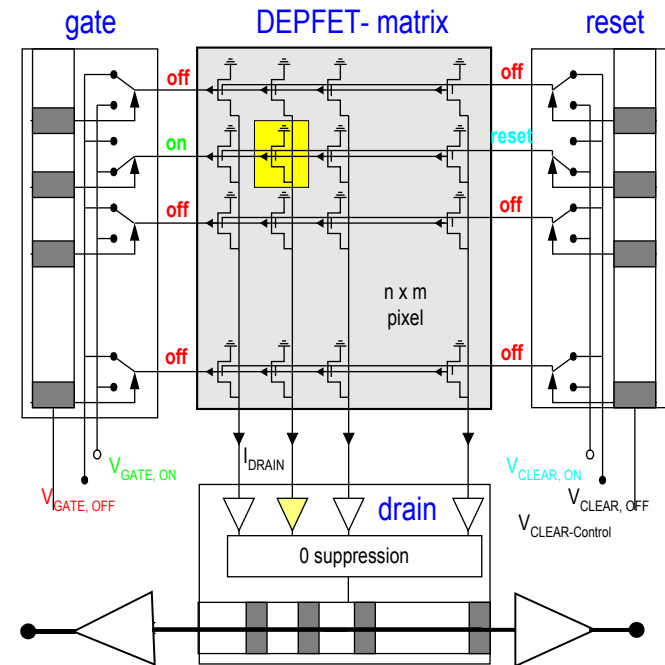
DEPFET (DEPFET collaboration)

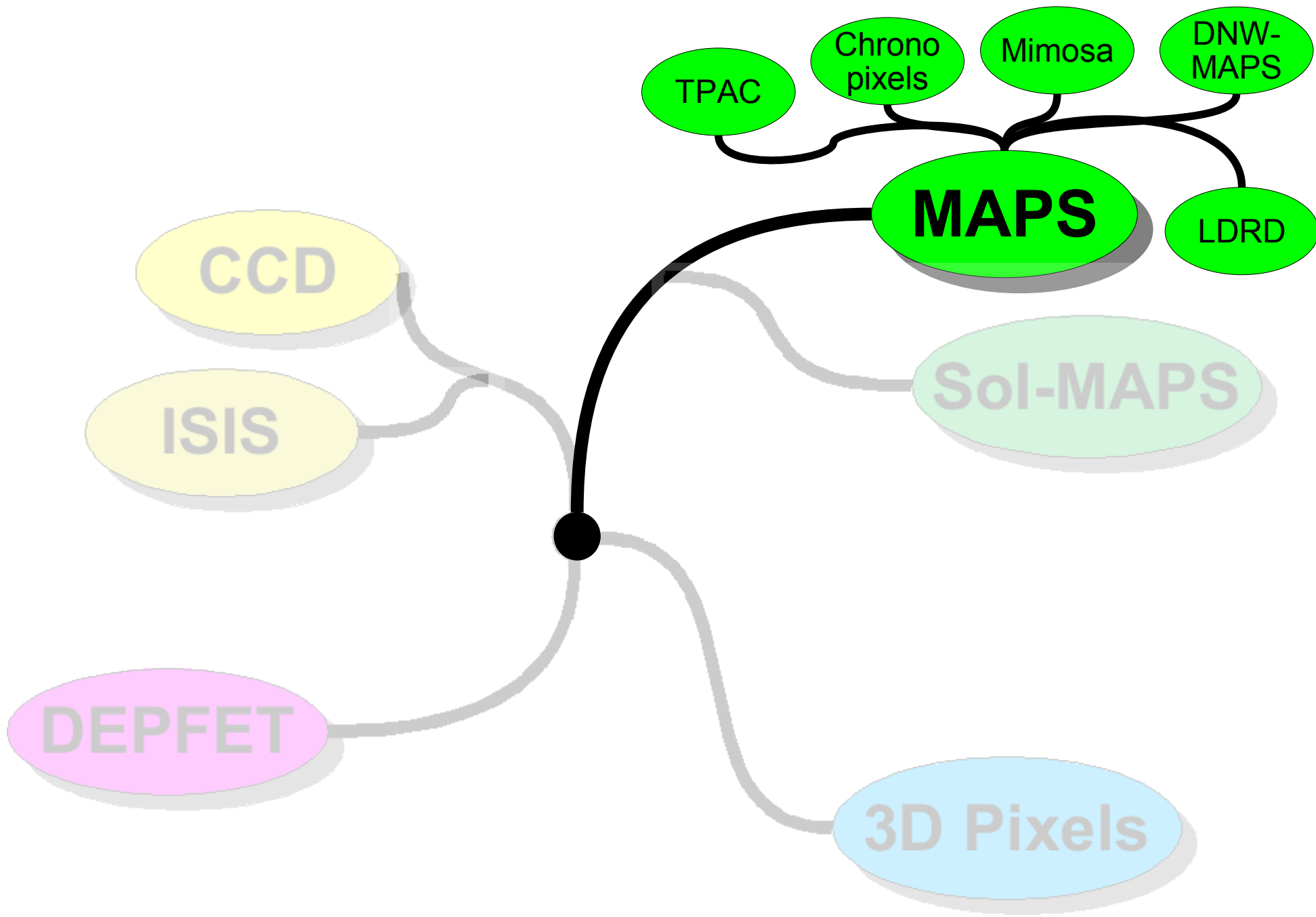
- **DE**pleted **P**-channel **FET**s
- Basic principle
 - Bulk fully depleted
 - Collection by drift
 - Internal gate collects charge
- Clear gate necessary
- Charge collection with FET's switched off, low power
- Unique process developed by MPI Halbleiterlabor



DEPFET Prototypes

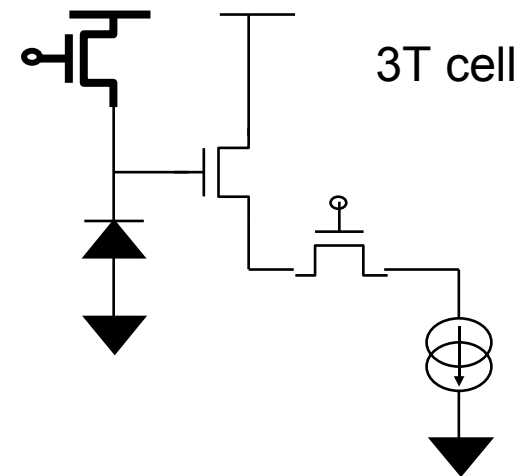
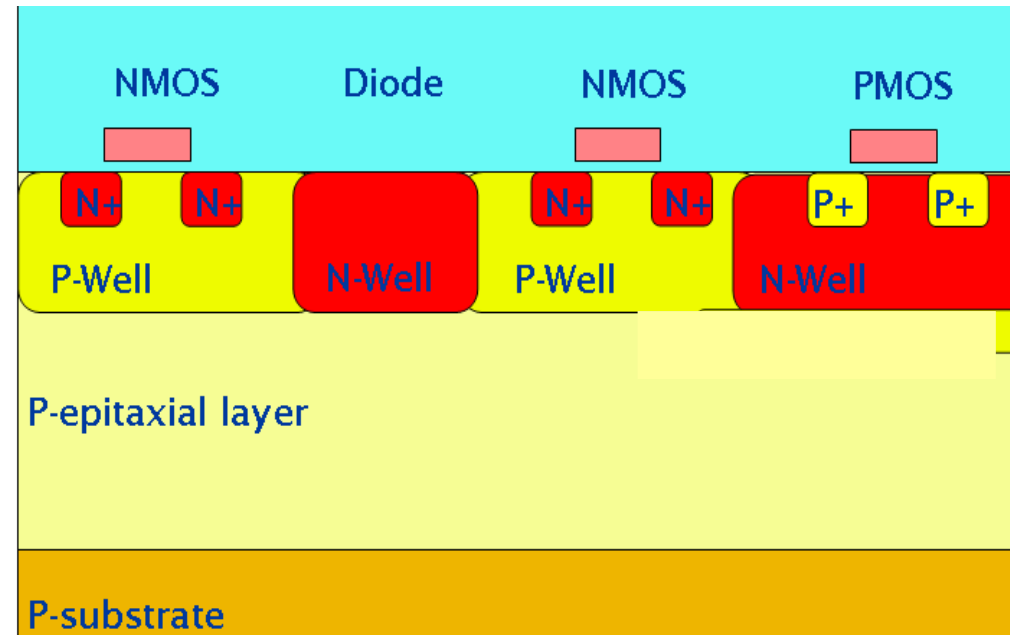
- DEPFET readout
 - External gate row select
 - Signal charge modifies current
 - CDS style readout using Clear gate
- Two driver ASICs needed
- Latest version PXD05
 - 24 μm pixel size
 - tests ongoing





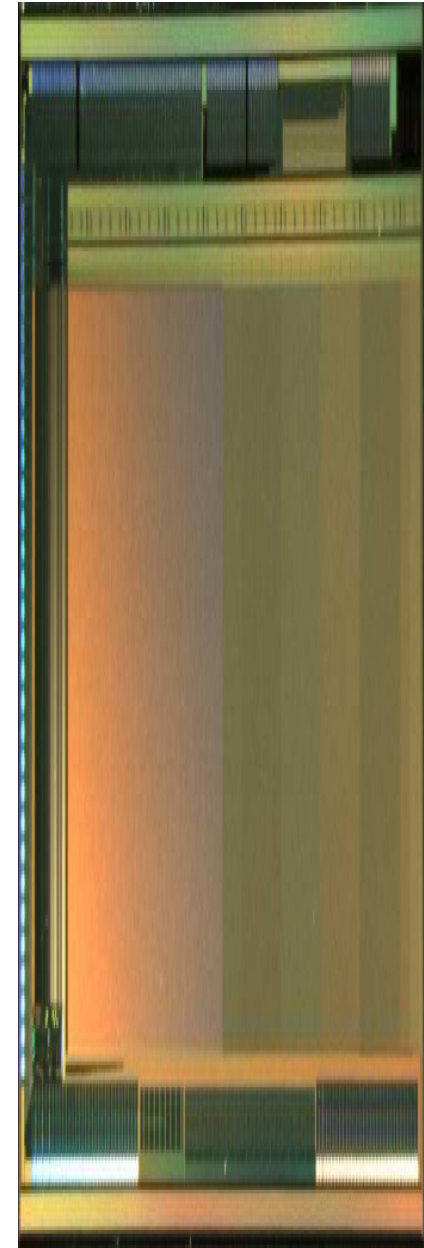
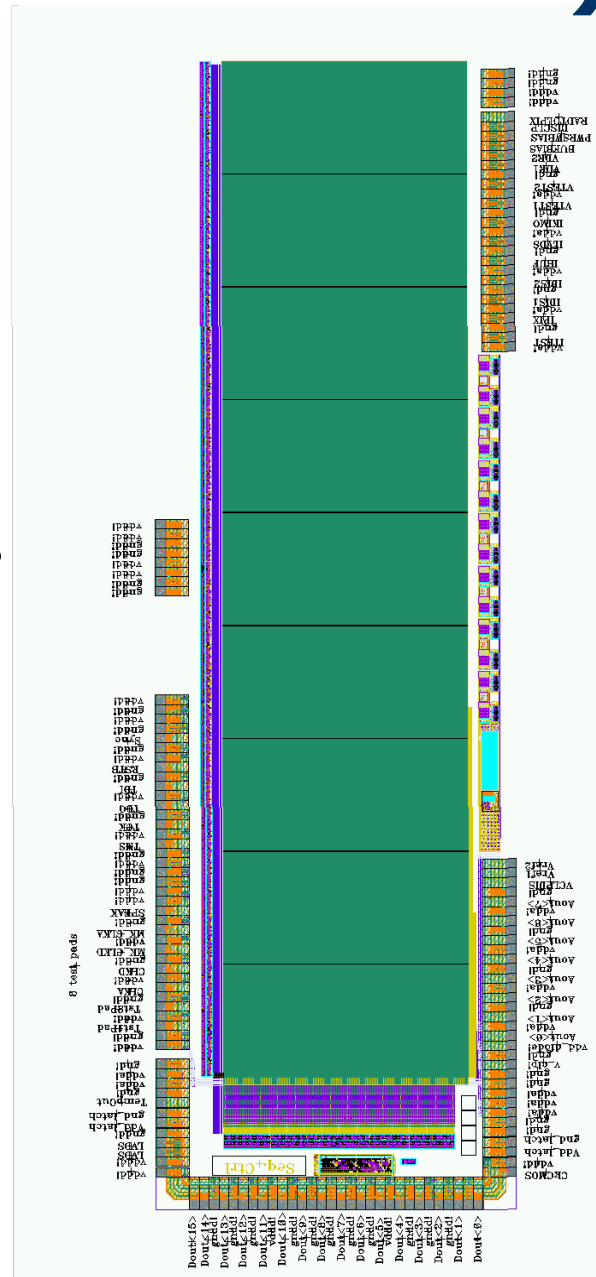
MAPS basic principle

- **M**onolithic **A**ctive **P**ixel **S**ensors
- CMOS technology
 - Down to 180 nm/130 nm
- Charge is collected by diffusion
 - Slow > 100 ns
- Integrated readout
- Parasitic charge collection
 - can't use PMOS ...
- Basic MAPS cell for Particle Physics
 - The 3T array



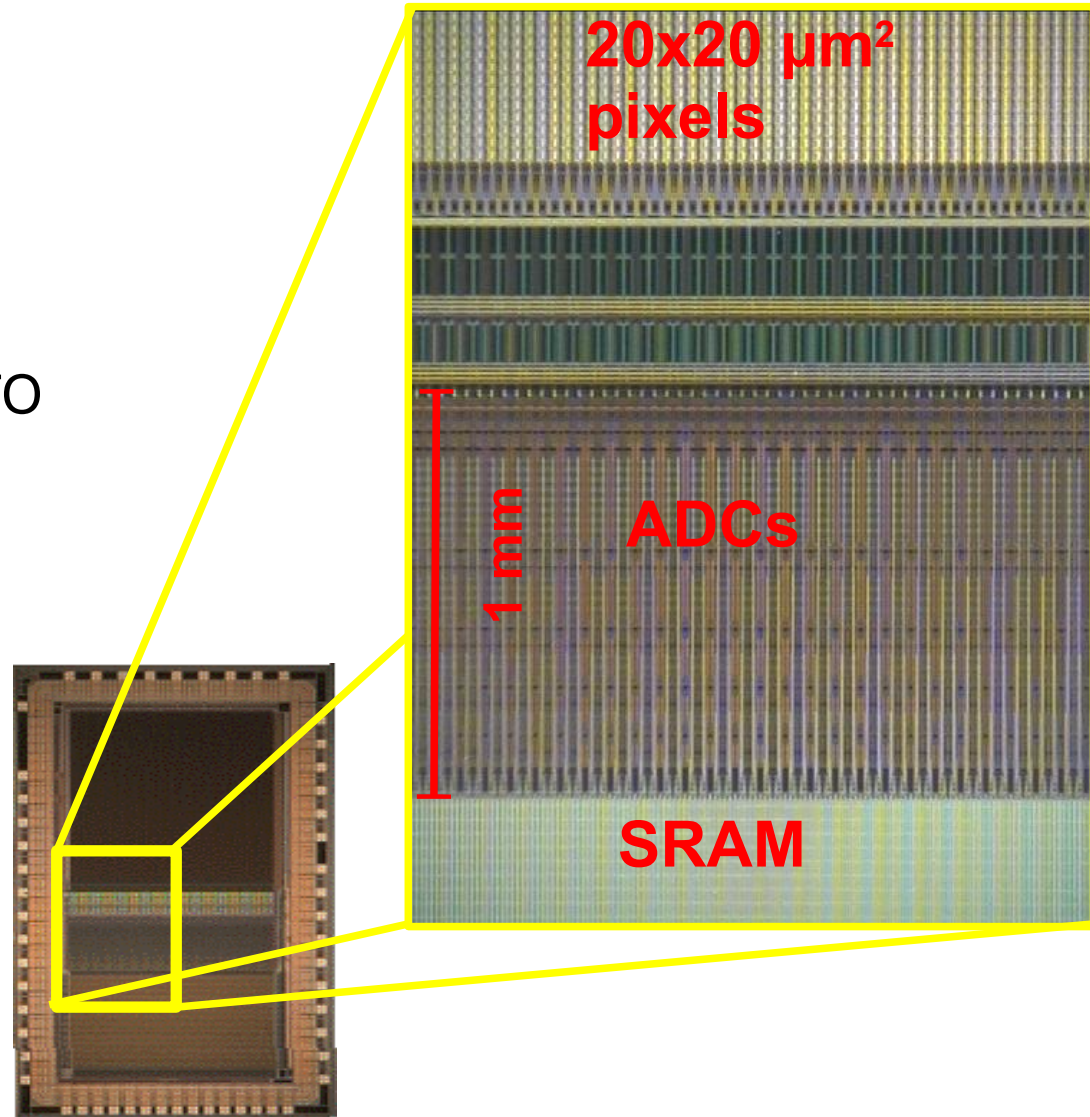
MIMOSA (IRES et. al.)

- MIMOSA family
 - 3T architecture
 - Restricted to NMOS
- MIMOSA 22
 - 0.35 μm AMS OPTO process
 - 18.4 μm pixel size
 - 128 columns
 - 128 x 576 pixels in total
 - Read-out time 100 μs
- Readout as Rolling-Shutter
 - One column read out at a time



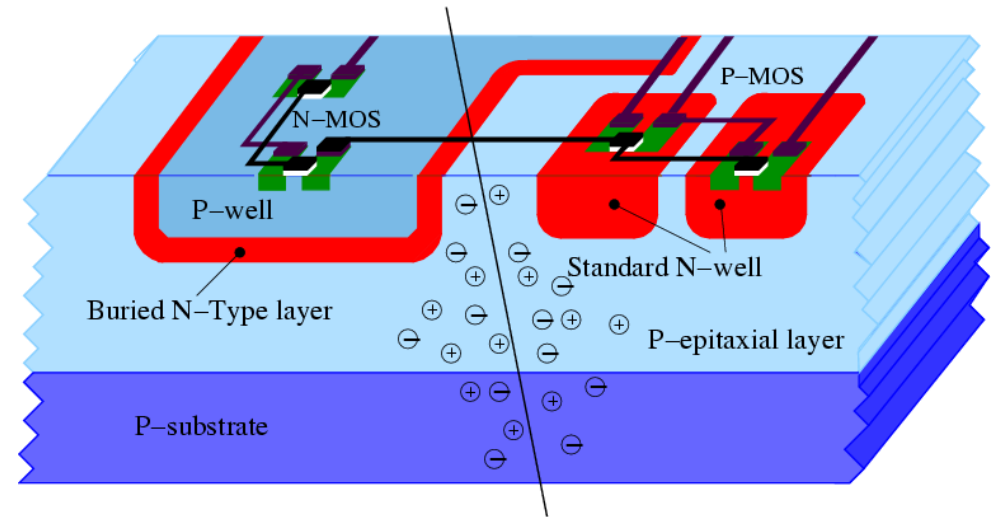
LDRD (LBNL et. al.)

- Current: LDRD03
 - 3T with in-pixel CDS
 - Readout at the end of a column
 - Made in 0.35 μm AMS OPTO process
 - 20 μm Pixels
 - 96 columns with 96 pixels each
- Rolling-Shutter readout

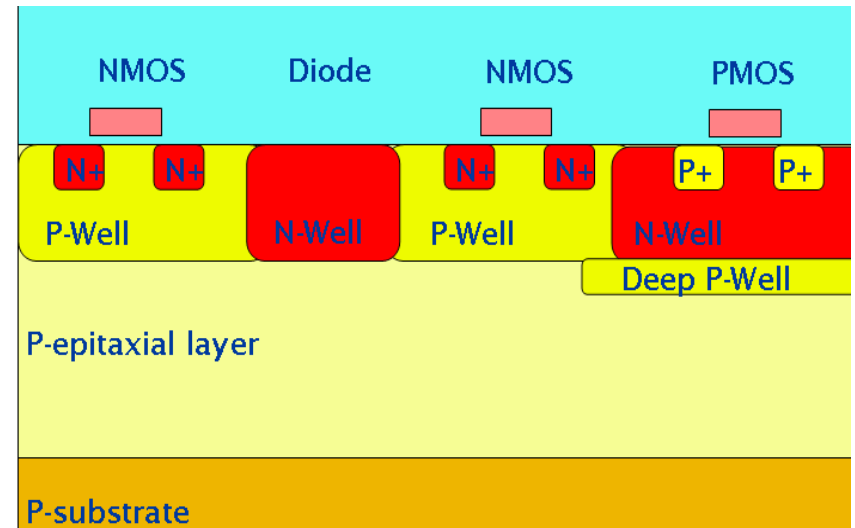


Overcoming the limits

- Two approaches
- Deep n-well
 - n-well diode as a deep implant covering most of pixel
 - Can have PMOS (small number)

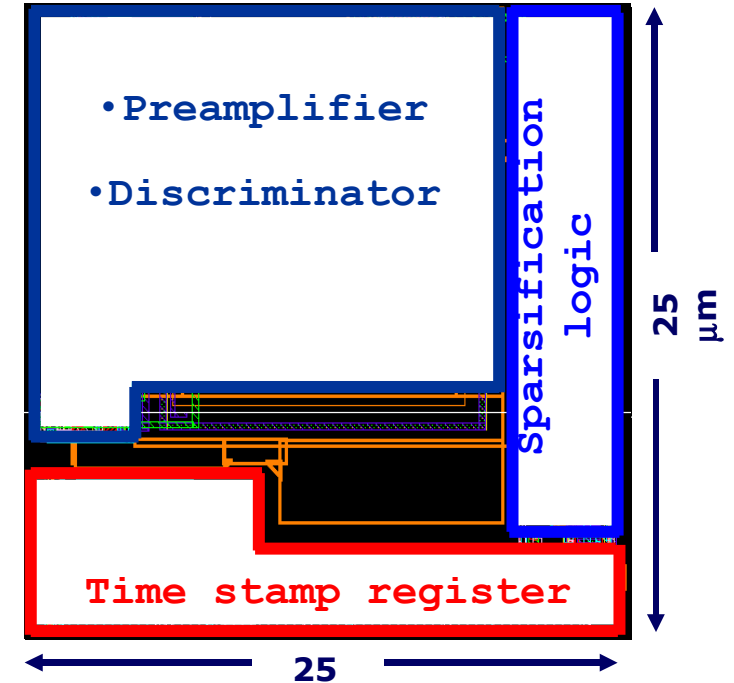
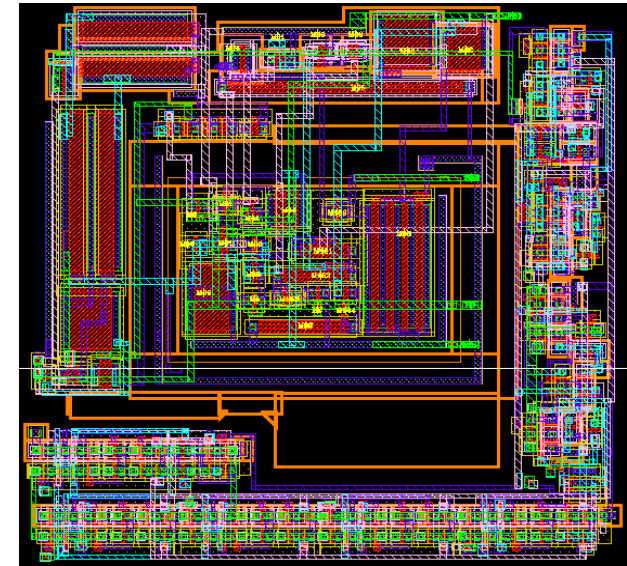


- Deep p-well
 - Encapsulate electronics n-wells with deep p-implant
 - shielding, so no parasitic charge collection
 - Realized e.g. in INMAPS process and in ISIS



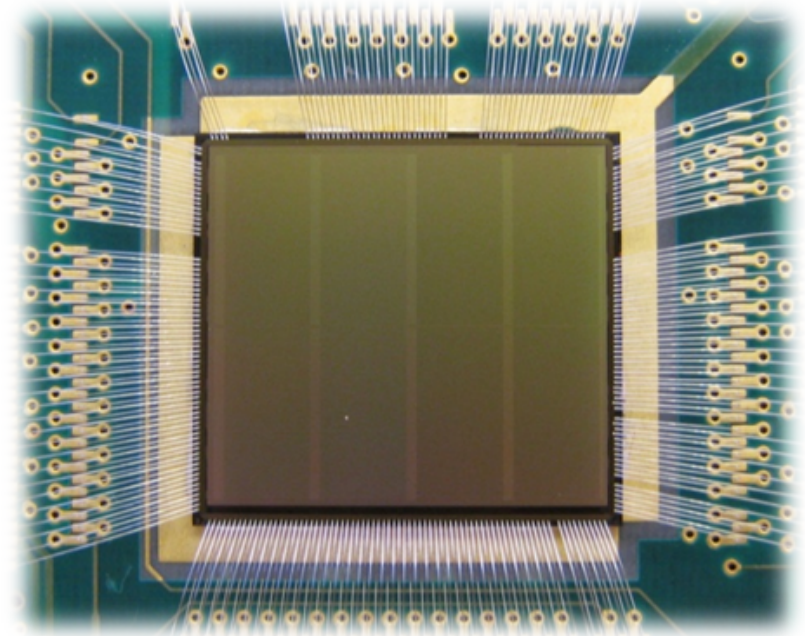
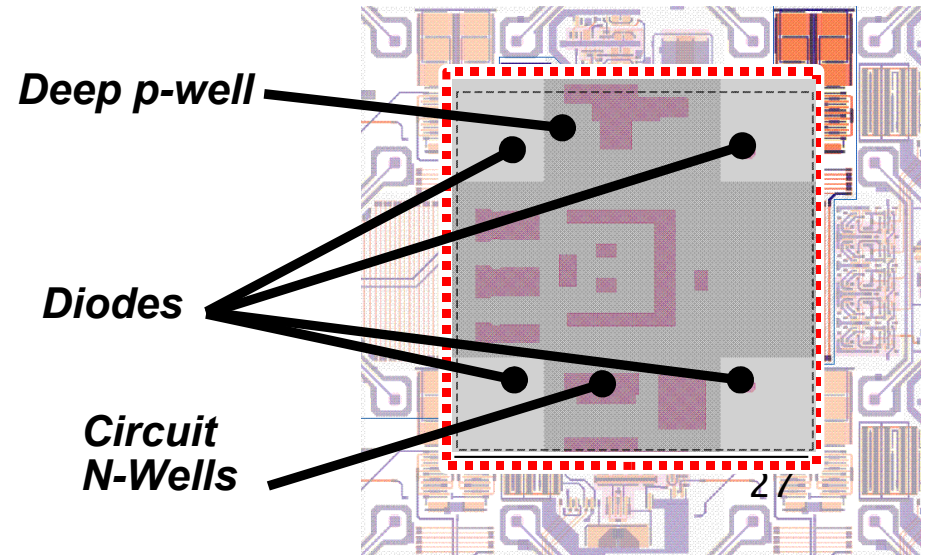
Deep n-Well MAPS (INFN)

- Made in ST 130 nm process
 - Triple-well approach
- 25 x 25 μm pixels with binary readout
 - Goal 15 x 15 μm
- Integrated electronics
 - Pre-amp, discriminator
 - Sparsification, time-stamping
- Plans to explore smaller feature sizes



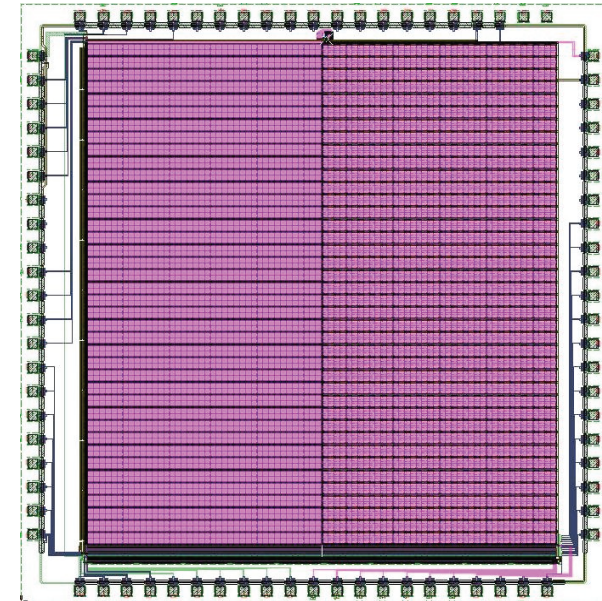
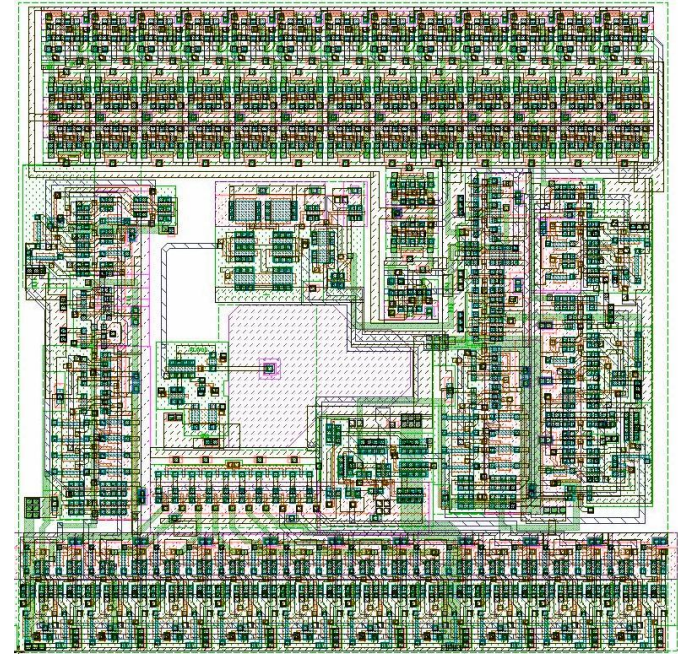
TPAC (CALICE-UK)

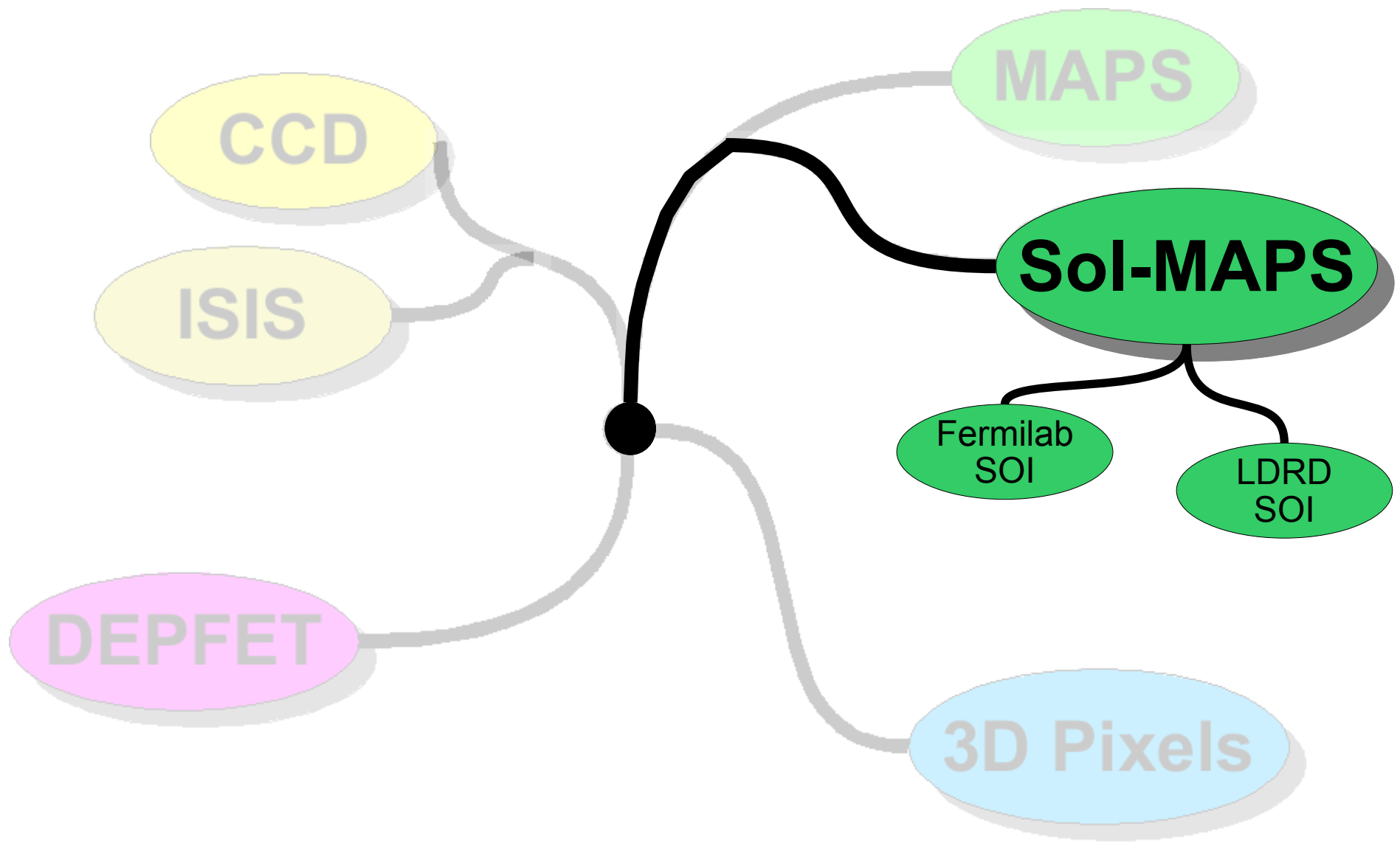
- 50 x 50 μm with binary readout
 - Deep p-well/INMAPS 180 nm
 - Pixel developed for digital EM calorimetry
 - Different optimization
- integrated electronics
 - Pre-amp, comparator
 - Pixel masks and trim
- Logic strips
 - Hold buffers and time-stamping
 - Add $\sim 11\%$ dead area



Chronopixels (Yale/Oregon)

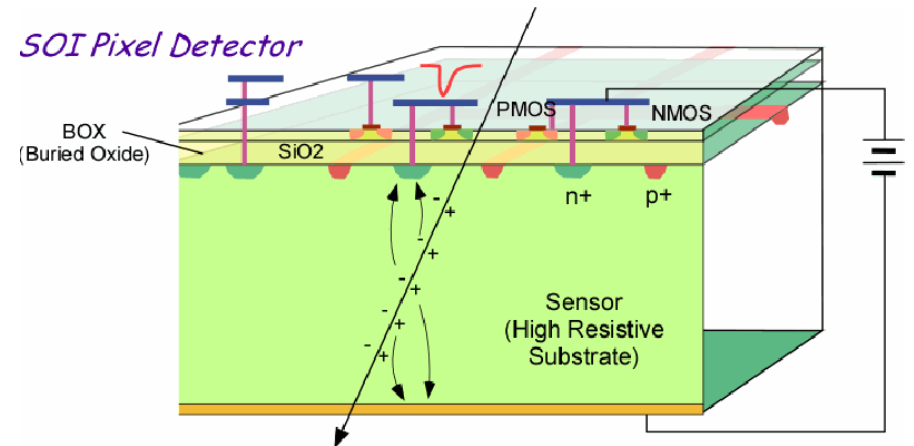
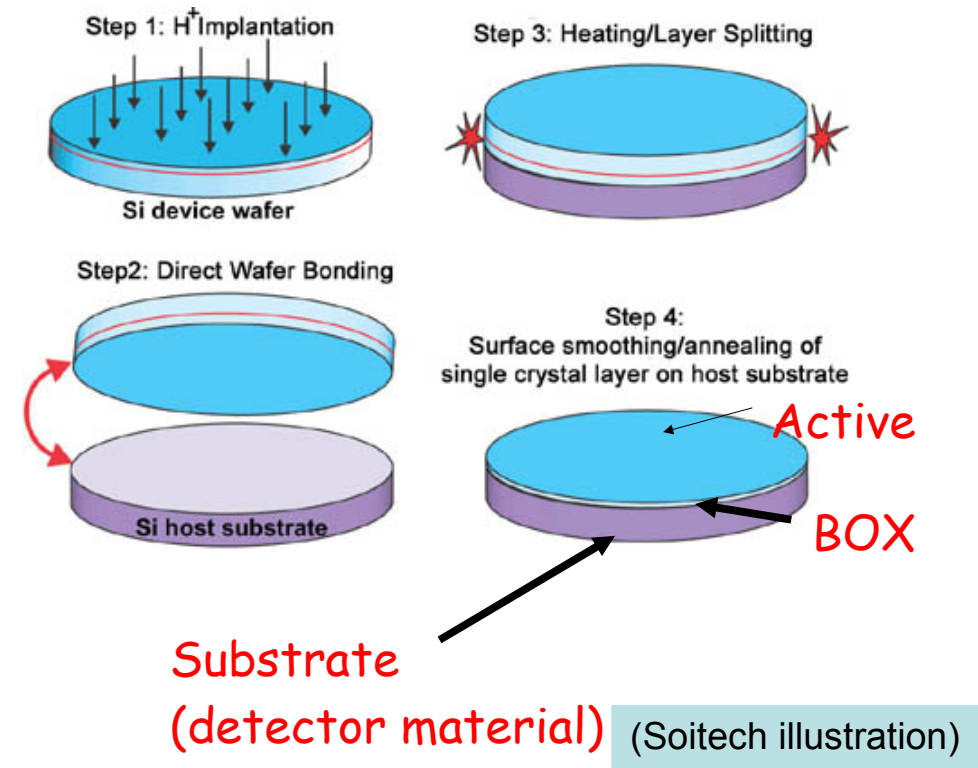
- Similar to previous pixels
 - In-pixel electronics
 - Hit buffering
 - Time-stamping
 - Binary readout
- Prototype made in 180 nm TSMC
 - Pixel size 50 x 50 μm
- Goal
 - 45 nm process
 - 10 x 10 μm pixels
 - Deep p-well and high-res epi





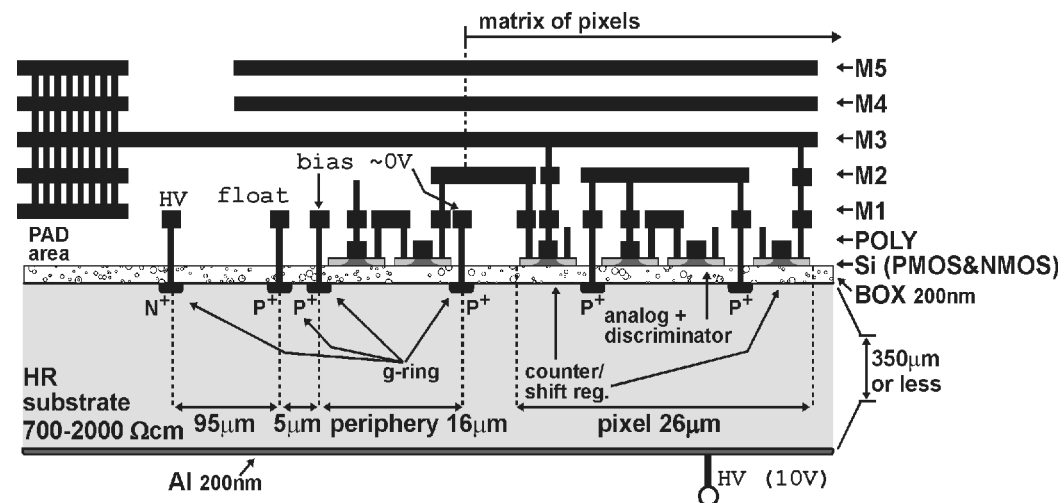
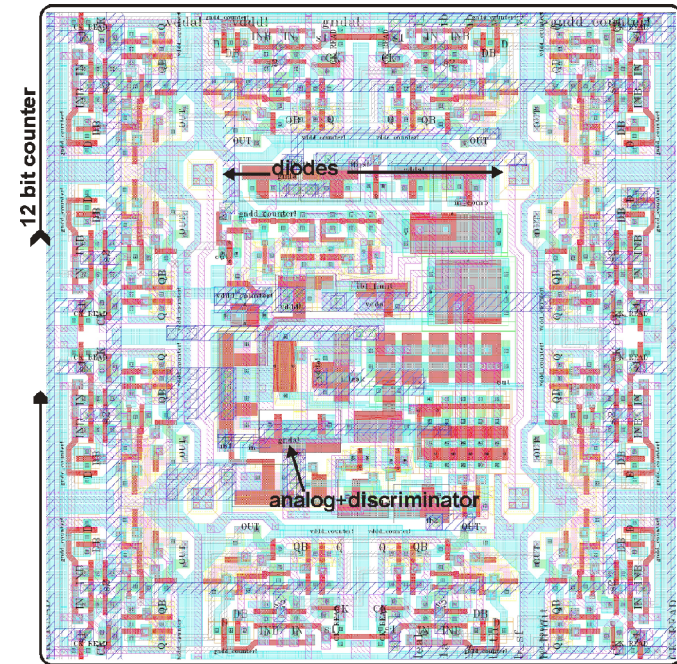
SoI Basics

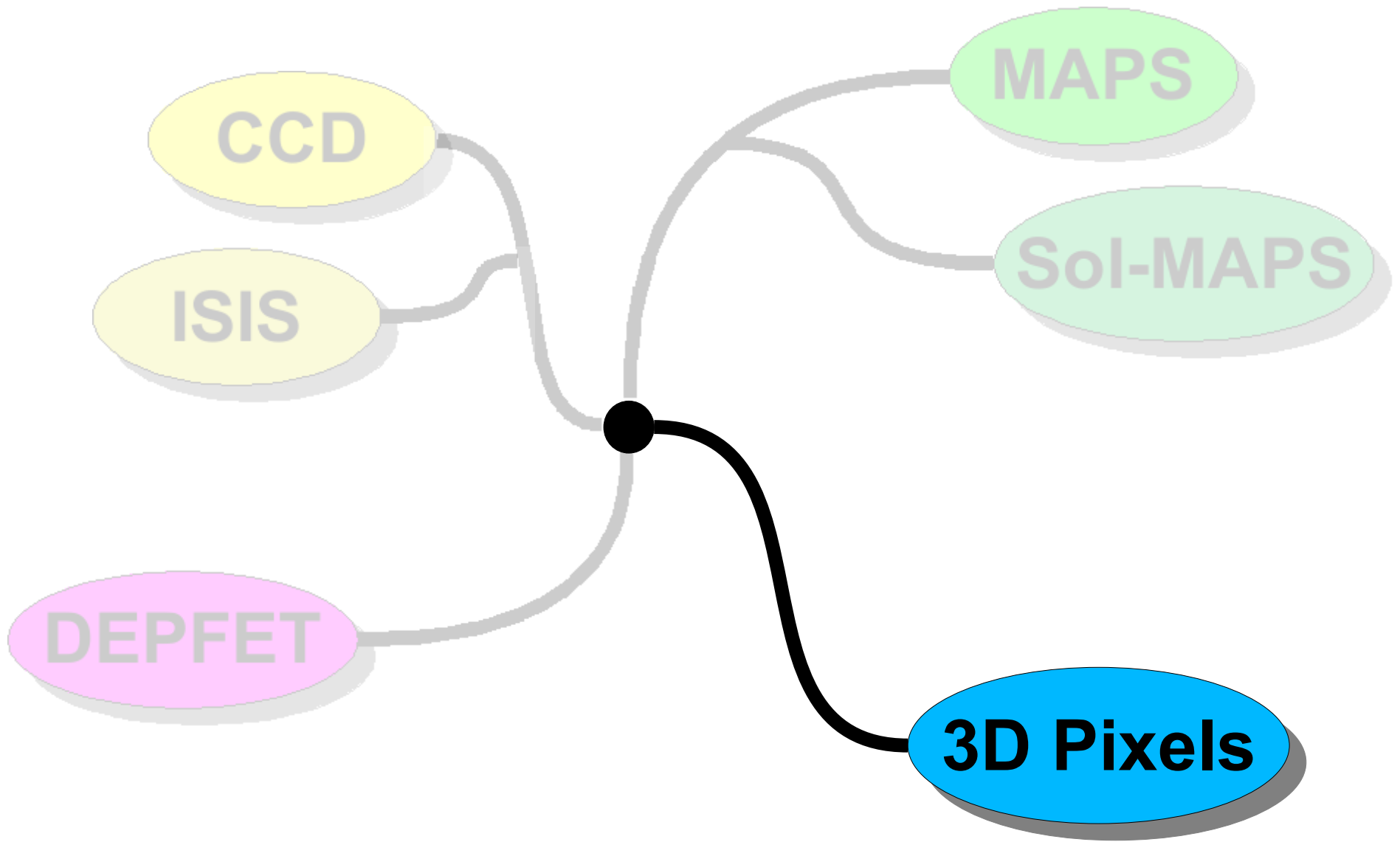
- **Silicon on Insulator (SoI)**
- Thin active circuit layer on insulating substrate
- ~200 nm of silicon on a "buried" oxide (BOX) carried on a "handle" wafer.
- Handle wafer can be high resistivity silicon
- Integration of electronics and fully depleted detectors in a single wafer
- Diode implant through the buried oxide



MAMBO (Fermilab)

- **M**onolithic **A**ctive pixel **M**atrix with **B**inary **c**ounters
- Made in 150 nm Oki Process
 - 200 nm BOX layer
- Pixel size is 26 x26 μm
 - Implements a 12 bit counter
- Common problem for all SoI
 - Backgate effect handling wafer
 - Can be fixed by using thicker BOX layer

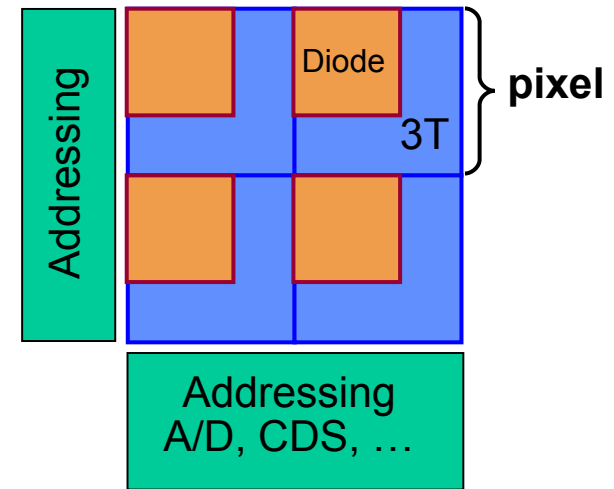




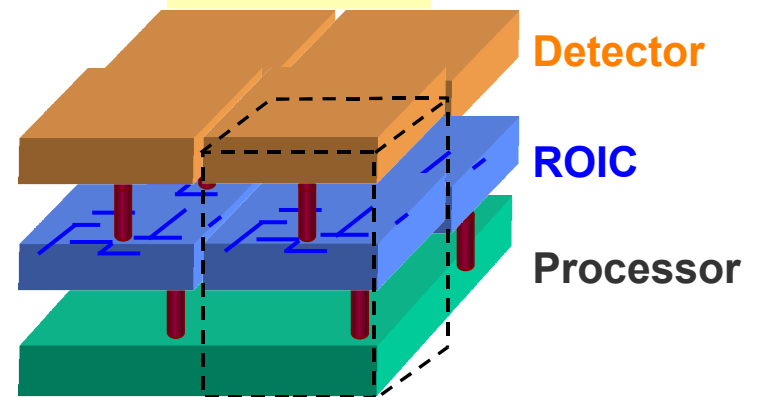
3D Pixels

- The ultimate dream of any pixel designer
 - Fully active sensor area
 - Independent control of substrate materials for each of the tiers
 - Fabrication optimized by layer function
 - In-pixel data processing
 - Increased circuit density due to multiple tiers of electronics
- A new way of doing things

Conventional MAPS

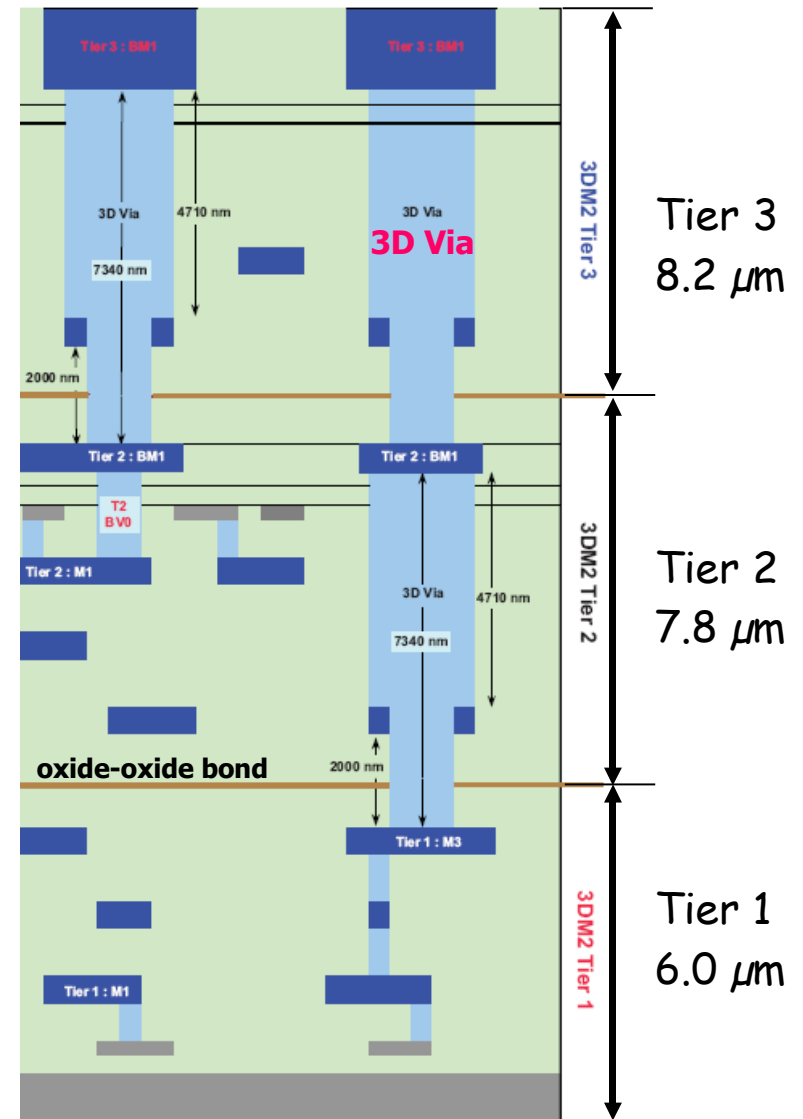


3-D Pixel



VIP-I (Fermilab)

- **V**ertically **I**ntegrated **P**ixel
- Pixel array 64x64, 20x20 μm pixels
 - Analog and binary readout
 - 5-bit Time stamping
 - Sparsification
- Designed for 1000 x 1000 array
- Chip divided into 3 tiers
- Made in MIT-LL process
- VIP2a is on its way



3D Process Developments

- The MIT LL process
 - Demonstrated a fully functional device
- However:
 - Poor yield- both processing problems and overly aggressive design
 - VIP2 will use degraded design rules (0.15 -> 0.2 or 0.3 μm) with improved transistor models
 - Analog SoI design is challenging
 - Long turn-around time
 - Not a commercial process
- Tezzaron 130 nm
 - Existing rules for vias and bonding
 - Relatively fast turn around
 - One stop shop for wafer fabrication, via formation, thinning, bonding
 - Low cost
 - Process is available to customers from all countries



Future Trends

- *Always in motion the future is ...*
 - especially for pixels
- **Higher integration**
 - Smaller features and 3D integration will make this possible
- **Larger sensor areas**
 - Real CMOS Stitching allow wafer-scale sensors
- **Low power designs**
 - Large pixel system will need to reduce power usage per channel



Which Technology ?

- Even more difficult to make a forecast
- For a vertex detector
 - Small area (1 m²) so choose technology that can do the job
 - Cost is a minor issue
- For trackers/ECAL etc
 - Industrial processes
 - Mass producible and cheap (large areas)
 - Minimize interconnects
- Interesting times ahead ...



Who is doing what

- **LCFI** (UK collaboration)
 - CPCCD/ISIS
- **FPCCD** group
 - FPCCD
- **DEPFET Collaboration**
 - DEPFET
- **LBNL/INFN/Purdue**
 - MAPS/SoI MAPS
- **Fermilab**
 - SoI MAPS/3D Pixels
- **CALICE-UK**
 - MAPS (TPAC)
- **CMOS-VD**
 - MAPS (MIMOSA)
- **Hawaii**
 - CAP
-



Summary

- If you like to know more ...
 - The ILC R&D reviews are an excellent summary of the activities
 - http://www.linearcollider.org/wiki/doku.php?id=drdp:drdp_home
- Thanks to
 - J. Brau, C. Damerell, M. Demarteau, T. Greenshaw, R. Lipton, K.D. Stefanov, Y. Sugimoto, R. Turchetta, M. Tyndel, N. Wermes for material, comments and discussion

